Amendment to the Claims

Please withdraw claims 8, 19, 22, and 54 without prejudice to consideration of these claims upon allowance of a generic claim. Following is a complete listing of claims, as amended:

1-6. (Canceled)

- 7. (Previously presented) A planarizing machine, comprising:
- a table having a support surface;
- a processing pad on the support surface;
- a carrier assembly having a head configured to hold a microelectronic workpiece and a drive assembly carrying the head relative to the support surface; and
- a solution dispenser separate from the head, the solution dispenser being configured to discharge a planarizing solution onto a plurality of locations on the pad, wherein the solution dispenser comprises: an elongated support extending over the pad at a location spaced apart from a travel path of the head; a fluid passageway carried by the support through which a planarizing solution can flow; and a fluid discharge unit slidably carried by the support and in fluid communication with the fluid passageway, the fluid discharge unit being moveable along the support to discharge a flow of the planarizing solution onto separate areas of the processing pad.
- 8. (Withdrawn) A planarizing machine, comprising:
- a table having a support surface;
- a processing pad on the support surface;
- a carrier assembly having a head configured to hold a microelectronic workpiece and a drive assembly carrying the head relative to the support surface; and

a solution dispenser separate from the head, the solution dispenser being configured to discharge a planarizing solution onto a plurality of locations on the pad, wherein the solution dispenser comprises a support extending over the pad at a location spaced apart from a travel path of the head, a fluid passageway carried by the support through which a planarizing solution can flow, and a nozzle carried by the support and in fluid communication with the fluid passageway, the nozzle being rotatably coupled to the support.

9-17. (Canceled)

- 18. (Previously presented) A planarizing machine, comprising:
- a table having a support surface;
- a processing pad on the support surface;
- a carrier assembly having a head configured to hold a microelectronic workpiece and a drive assembly carrying the head; and
- a solution dispenser separate from the head, the solution dispenser having a support extending over the pad and a distributor carried by the support, the distributor being configured to discharge a planarizing solution from a plurality of locations along the support, wherein the support comprises an elongated arm and a fluid passageway carried by the arm through which a planarizing solution can flow, and the distributor further comprises a fluid discharge unit slidably carried by the arm and in fluid communication with the fluid passageway, the fluid discharge unit being moveable along the arm to discharge a flow of the planarizing solution along different areas of the processing pad.
- 19. (Withdrawn) A planarizing machine, comprising:
- a table having a support surface;
- a processing pad on the support surface;

a carrier assembly having a head configured to hold a microelectronic workpiece and a drive assembly carrying the head; and

- a solution dispenser separate from the head, the solution dispenser having a support extending over the pad and a distributor carried by the support, the distributor being configured to discharge a planarizing solution from a plurality of locations along the support, wherein the support comprises an elongated arm and a fluid passageway carried by the arm through which a planarizing solution can flow, and the distributor further comprises a nozzle carried by the arm and in fluid communication with the fluid passageway, the nozzle being rotatably coupled to the arm.
- 20. (Original) A planarizing machine, comprising:
- a table having a support surface;
- a processing pad on the support surface;
- a carrier assembly having a head configured to hold a microelectronic workpiece and a drive assembly carrying the head; and
- a solution dispenser having support above the pad and a nozzle moveably coupled to the support, the nozzle being coupleable to a planarizing solution.
- 21. (Original) The planarizing machine of claim 20 wherein:
- the support comprises an elongated arm and a fluid passageway carried by the arm through which a planarizing solution can flow; and
- the nozzle is slidably carried by the arm and in fluid communication with the fluid passageway.
- 22. (Withdrawn) The planarizing machine of claim 20 wherein:
- the support comprises an elongated arm and a fluid passageway carried by the arm through which a planarizing solution can flow; and the nozzle is rotatably coupled to the arm.

23-51. (Canceled)

52. (Previously presented) A method of processing a microelectronic workpiece, comprising:

removing material from the workpiece by pressing the workpiece against a contact surface of a processing pad and imparting relative motion between the workpiece and the contact surface; and discharging a planarizing solution directly onto a first region of the contact surface and concurrently discharging the planarizing solution directly onto a second region of the contact surface separate from the first region, the planarizing solution being deposited onto the first and second regions separate from a head carrying the workpiece, wherein discharging the . planarizing solution comprises (a) passing the planarizing solution through a fluid discharge unit that is moveably carried by a support over the processing pad and (b) concurrently moving the fluid discharge unit relative to the support to discharge the planarizing fluid at different regions across the contact surface.

- 53. (Original) The method of claim 52 wherein moving the fluid discharge unit comprises sliding the fluid discharge unit along the support.
- 54. (Withdrawn) The method of claim 52 wherein moving the fluid discharge unit comprises rotating the fluid discharge unit about a pivot point on the support.
 - 55. (Canceled)